

2006 VLSI Technology Short Course
TAPA I/II

Process Technologies for Continued
Scaling and Performance

Monday, June 12, 2006, 9:00 a.m.

Organizers: Robert Chau, Intel Corporation
Toshihiro Sugii, Fujitsu Laboratories, Ltd.

- 9:00 a.m. Back-end Interconnect Technology**
C.H. Jan, Intel Corp.
- 10:00 a.m. Break**
- 10:15 a.m. Advanced Embedded Memories**
K. Ishimaru, Toshiba Corp.
- 11:15 a.m. Lithography Solutions for 32nm and Beyond**
M. Kameyama, Nikon Corp.
- 12:15 p.m. Lunch**
- 2:00 p.m. Ultra-Shallow Junction Technologies**
M. Kase, Fujitsu, Ltd.
- 3:00 p.m. Device Technology**
S. Thompson, University of Florida
- 4:00 p.m. Break**
- 4:15 p.m. High-k Gate Dielectrics**
J. Lee, University of Texas at Austin
- 5:15 p.m. Conclusion**